

*54.* (amended) A method for forming a relief image on a substrate comprising:  
applying on the substrate a layer of an antihalation composition comprising an  
anthracene material;

*B2* applying over the antihalation composition coating layer a photoresist composition.

*6.*  
*55.* (amended) The method of claim *54* wherein the antihalation composition  
coating layer is crosslinked prior to applying the photoresist composition.

*[ ]* Please add the following new claims.

*13.*  
*58.* The method of claim *54* wherein the photoresist composition is imaged with  
activating radiation and the imaged photoresist composition is treated with a developer to  
provide a photoresist relief image.

*14.*  
*59.* The method of claim *58* wherein areas bared of photoresist upon treatment with  
the developer are etched.

*15.*  
*60.* The method of claim *58* wherein areas bared of photoresist upon treatment with  
the developer are exposed to a plasma gas.

*B3* *61.* The method of claim *58* wherein the plasma gas penetrates the antihalation  
composition coating layer.

*62.* The method of claim *55* wherein the photoresist composition is imaged with  
activating radiation and the imaged photoresist composition is treated with a developer to  
provide a photoresist relief image.